

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims, including those in the First Preliminary Amendment, in the application:

**Listing of Claims:**

Claim 1 (currently amended): A high purity Ru powder wherein the content of the respective alkali metal elements such as Na and K is 10 wtpm or less, and the content of Al is in the range of [1]  $\leq$  50 wtpm.

Claims 2-7 (canceled).

Claim 8 (new): A high purity Ru powder according to claim 1, wherein the content of Al is in the range of 5 to 20 wtpm.

Claim 9 (new): A high purity Ru powder according to claim 8, wherein the total content of transition metal elements is 100 wtpm or less, and the respective content of radioactive elements is 10 wtpb or less.

Claim 10 (new): A high purity Ru powder according to claim 9, wherein the purity excluding oxygen, nitrogen, and hydrogen gas components is 99.99% or higher.

Claim 11 (new): A high purity Ru powder according to claim 10, wherein the content of oxygen is 100 wtpm or less.

Claim 12 (new): A high purity Ru powder according to claim 1, wherein the total content of Fe, Ni, Co, Cr and Cu is 100 wtppm or less, and the respective content of U and Th is 10 wtpb or less.

Claim 13 (new): A high purity Ru powder according to claim 1, wherein the purity excluding gas components is 99.99% or higher.

Claim 14 (new): A high purity Ru powder according to claim 13, wherein the content of oxygen is 100 wtppm or less.

Claim 15 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target wherein the respective content of alkali metal elements such as Na and K is 10 wtppm or less, and the content of Al is in the range of 5 to 50 wtppm.

Claim 16 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 15, wherein the content of Al is in the range of 5 to 20 wtppm.

Claim 17 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 16, wherein the total content of transition metal elements is 100 wtppm or less, and the respective content of radioactive elements is 10 wtpb or less.

Claim 18 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 17, wherein the purity excluding oxygen, nitrogen and hydrogen gas components is 99.99% or higher.

Claim 19 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 18, wherein the content of oxygen is 100 wtpm or less.

Claim 20 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 15, wherein the total content of Fe, Ni, Co, Cr and Cu is 100 wtpm or less, and the respective content of U and Th is 10 wtpb or less.

Claim 21 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 15, wherein the purity excluding gas components is 99.99% or higher.

Claim 22 (new): A high purity Ru sputtering target or high purity Ru thin film formed from the sputtering target according to claim 21, wherein the content of oxygen is 100 wtpm or less.

Claim 23 (new): A method of manufacturing high purity Ru powder, comprising the steps of using an Ru raw material having a purity of 3N (99.9%) or less as an anode during electrolytic refining, and performing said electrolytic refining in a solution to produce a high

purity Ru powder wherein the respective content of alkali metal elements in the powder is 10 wtpm or less and a content of Al in the powder is in a range of 5 to 50 wtpm.

Claim 24 (new): A method according to claim 23, wherein the content of Al in the powder is in the range of 5 to 20 wtpm.

Claim 25 (new): A method according to claim 23, wherein the total content of transition metal elements in the powder is 100 wtpm or less, and the respective content of radioactive elements in the powder is 10 wtpb or less.

Claim 26 (new): A method according to claim 23, wherein the purity of the powder excluding gas components is 99.99% or higher and the content of oxygen in the powder is 100 wtpm or less.